

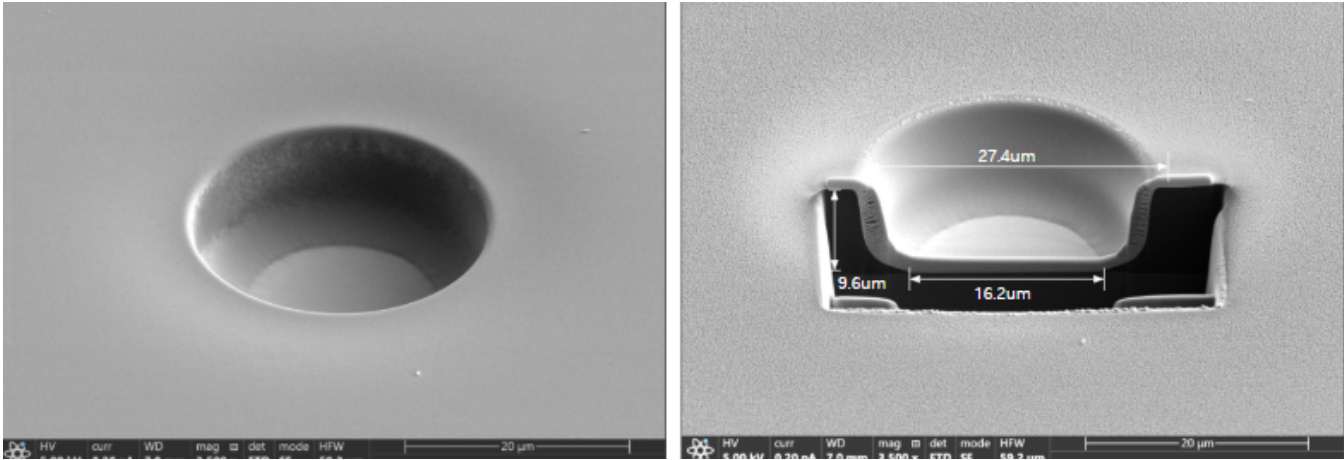
Coating and Patternability Evaluation

Evaluating photosensitive material patterns involves assessing the quality and characteristics of patterns formed on or within these materials after exposure to light. This evaluation can include analyzing the pattern's dimensions, shape, resolution, and uniformity, as well as the material's properties after the patterning process. Key aspects of evaluation often involve microscopy, profilometry, and spectroscopic techniques to understand the material's response to light and the resulting pattern formation. Here's a more detailed breakdown:

1. Pattern Definition and Dimensions:

Microscopy:

Optical microscopy and electron microscopy (SEM/TEM) are used to visualize the patterns and measure their dimensions, such as line widths, spaces, and feature sizes.



Profilometry:

Techniques like stylus profilometry or atomic force microscopy (AFM) are used to measure the surface topography of the patterned material and determine the depth and shape of features.

